

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	HIGH-PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER						
Application Number :	10/680783						
Confirmation Number:	5859						
First Named Applicant:	William Jones						
Attorney Docket Number:							
Art Unit:							
Examiner:							
Search string:	(4391511 or 6722642).pn						
<p><u>Certification:</u> This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:</p> <p>That each item of information contained in the information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.</p>							
US Patent Documents							
<p>Note: Applicant is not required to submit a paper copy of cited US Patent Documents</p>							
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	4391511	1983-07-05	Akiyama et al.			
	2	6722642	2004-04-20	Sutton et al.	B1		
Signature							
Examiner Name				Date			